#### FYS3410 - Vår 2016 (Kondenserte fasers fysikk)

http://www.uio.no/studier/emner/matnat/fys/FYS3410/v16/index.html

Pensum: Introduction to Solid State Physics by Charles Kittel (Chapters 1-9 and 17, 18, 20)

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#### 2016 EVS3/110 Lectures (based on C Kittel's Introduction to SSP Chanters 1-9, 17,18,20)

3h

3h

2h 1h 2h

1h 2h 1h 2h

3h 1h 2h

> 1h 2h 1h 1h 2h

2h 1h 2h

1h 3h 1h 3h 1h 3h 1h 3h

2h

2016 FYS341	0 Lectures (based on C.Kittel's Introduction to SSP, Chapters 1-9, 17,18,20)				
	odic Structures and Defects (Chapters 1-3, 20)				
M18/1: 9-12 am	Introduction. Crystal bonding. Periodicity and lattices, Brag diffraction and Laue condition, reciprocal space				
W20/1 cancelled M25/1: 9-12 am	Ewald construction, interpretation of a diffraction experiment, Brag planes, and Brillouin zones				
W27/1 cancelled	Ewald Constituction, interpretation of a dimaction experiment, brag planes, and brillouin Zones				
M01/2: 10-12 am	Elastic strain and structural defects in crystals				
W03/2: 9-10 am	Atomic diffusion in solids				
M08/2: 10-12 am	Summary of Module I				
Module II - Pho	nons (Chapters 4 and 5)				
W10/2: 9-10 am	Vibrations in monoatomic and diatomic chains of atoms				
M15/2: 10-12am	Periodic boundary conditions, phonons and density of states (DOS)				
W17/2: 9-10 am	Planck distribution				
M22/2: 10-12am	Lattice heat capacity: Dulong-Petit, Einstein, and Debye models				
W24/2 cancelled M29/2: 9-12am	Comparison of different models for lattice heat capacity, thermal conductivity with phonons				
W02/3: 9-10 am	Thermal expansion				
M07/3: 10-12am	Summary of Module II.				
	ctrons (Chapters 6, 7, 18 - pp.528-530, and Appendix D)				
W09/3: 9-10 am	Free electron gas (FEG) versus free electron Fermi gas (FEFG)				
M14/3: 10-12am	DOS of FEFG in 3D. Effect of temperature – Fermi-Dirac distribution				
W16/3: 9-10 am	Heat capacity of FEFG in 3D				
W30/3: 9-10 am	DOS in 2D - quantum wells				
M04/4: 10-12am	DOS in 1D and 0D, i.e. quantum wires and quantum dots; transport properties of electrons				
W06/4: 9-10 am	Origin of the energy band gap				
M11/4: 10-12am	Nearly free electron model. Kronig-Penney model. Empty lattice approximation.				
W13/4: 9-10 am	Number of orbitals in a band				
M18/4: 10-12am	Summary of Module III.				
	miconductors and interfaces (Chapters 8, 9-pp 223-231, 17)				
W20/4: 9-10 am	Metals versus semiconductors. Surfaces and interfaces.				
M25/4: 9-12 am	Effective mass method.				
W27/4: 9-10 am	Intrinsic carrier generation – eletrons and holes.				
M02/5: 9-12 am W04/5: 9-10 am	Localized levels for hydrogen-like impurities – donors and acceptors. Doping.  Carrier statistics in semiconductors				
M09/5: 9-12 am	p-n junctions				
	Optoelectronic semiconductor properties and devices				
	Device demonstrations. Summary of Module IV				
Repetition					
	The course in a nutshell				
W25/5, M30/5 and					
Exam during week 22 (tentatively 30-31/5)					

**Lecture: P-N junction** 

- Repetition: intrinsic and extrinsic semiconductors
- Charge carrier transport mechanisms diffusion and drift
- Band bending as a function of carrier concentration
- P-N junction in equilibrium
- Gauss and Poisson equations for the depletion region
- •P-N junction with applied external bias

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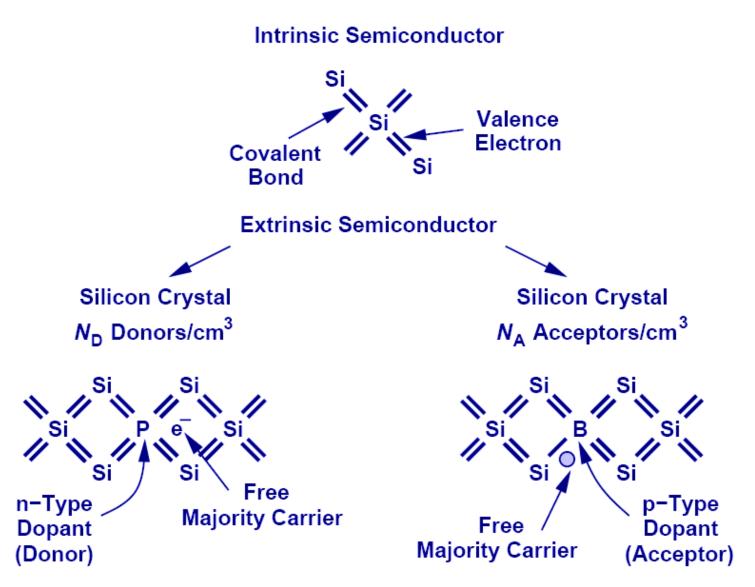
#### **Intrinsic and extrinsic semiconductors**

		III	IV	V	
		Boron (B)	Carbon (C)		
• •	•	Aluminum (Al)	Silicon (Si)	Phosphorous (P)	
		Galium (AI)	Germanium (Ge)	Arsenic (As)	
			•		

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#### Intrinsic and extrinsic semiconductors

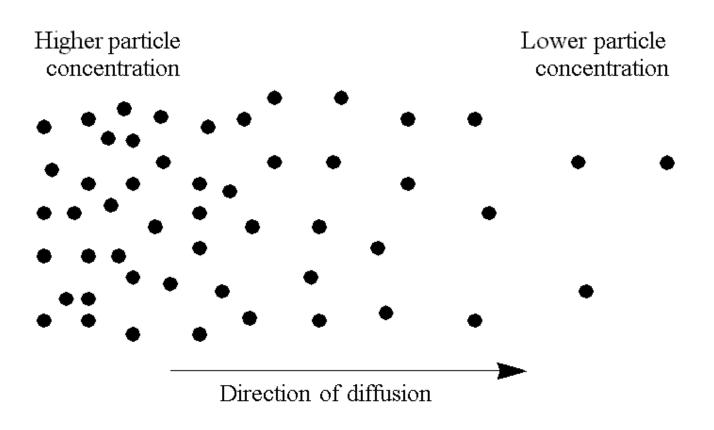


# **Lecture: P-N junction**

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#### Diffusion of charge carriers

Particles diffuse from regions of higher concentration to regions of lower concentration region, due to random thermal motion.



#### Diffusion of charge carriers

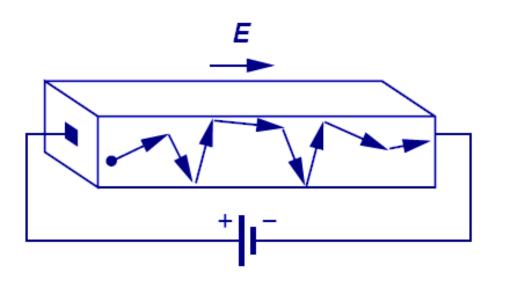
$$J_{\text{n,diff}} = qD_n \frac{dn}{dx}$$

$$J_{\text{p,diff}} = -qD_p \frac{dp}{dx}$$

$$\downarrow p$$

D is the diffusion constant, or diffusivity.

#### **Drift of charge carriers**



$$\overrightarrow{v_h} = \mu_p \overrightarrow{E}$$

$$\overrightarrow{v_e} = -\mu_n \overrightarrow{E}$$

- The process in which charge particles move because of an electric field is called drift.
- Charge particles will move at a velocity that is proportional to the electric field.

# **Diffusion** + **drift** of charge carriers

$$J = J_n + J_p$$

$$J_{n} = J_{n,drift} + J_{n,diff} = qn\mu_{n}\mathcal{E} + qD_{n}\frac{dn}{dx}$$

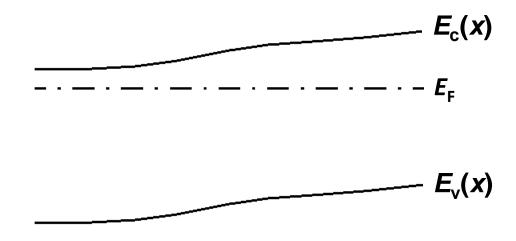
$$\boldsymbol{J}_{p} = \boldsymbol{J}_{p,drift} + \boldsymbol{J}_{p,diff} = qp\mu_{p}\mathcal{E} - qD_{p}\frac{dp}{dx}$$

# **Lecture: P-N junction**

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# Band bending as a function of carrier concentration

- The position of E<sub>F</sub> relative to the band edges is determined by the carrier concentrations, which is determined by the net dopant concentration.
- In equilibrium E<sub>F</sub> is constant; therefore, the band-edge energies vary with position in a non-uniformly doped semiconductor:

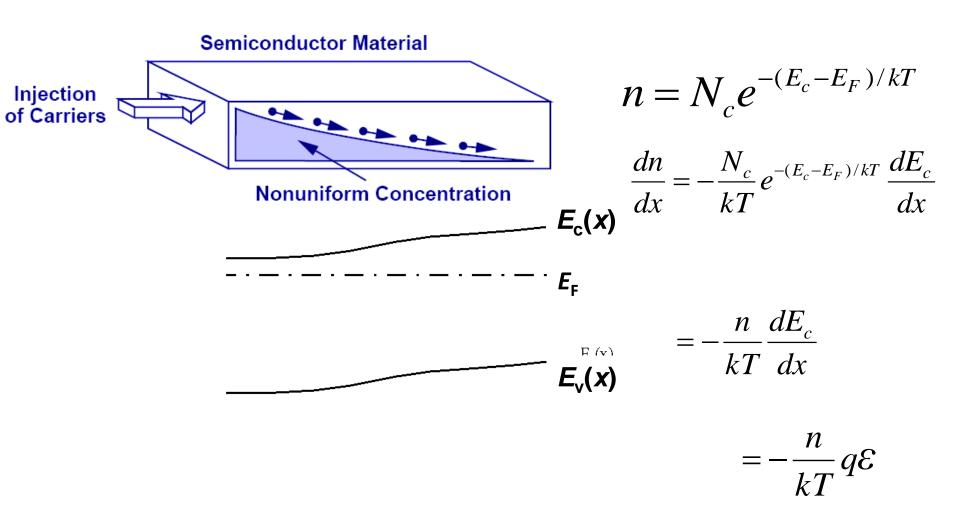


# Band bending as a function of carrier concentration

The ratio of carrier densities at two points depends exponentially on the potential difference between these points:

$$\begin{split} E_{\mathrm{F}} - E_{\mathrm{i}1} &= kT \ln \left( \frac{n_{\mathrm{1}}}{n_{\mathrm{i}}} \right) \\ &= > E_{\mathrm{i}1} = E_{\mathrm{F}} - kT \ln \left( \frac{n_{\mathrm{1}}}{n_{\mathrm{i}}} \right) \\ &= \mathrm{Similarly}, \quad E_{\mathrm{i}2} = E_{\mathrm{F}} - kT \ln \left( \frac{n_{\mathrm{2}}}{n_{\mathrm{i}}} \right) \\ &= \mathrm{Therefore} \quad E_{\mathrm{i}1} - E_{\mathrm{i}2} = kT \left[ \ln \left( \frac{n_{\mathrm{2}}}{n_{\mathrm{i}}} \right) - \ln \left( \frac{n_{\mathrm{1}}}{n_{\mathrm{i}}} \right) \right] = kT \ln \left( \frac{n_{\mathrm{2}}}{n_{\mathrm{1}}} \right) \\ &= V_{2} - V_{1} = \frac{1}{a} \left( E_{\mathrm{i}1} - E_{\mathrm{i}2} \right) = \frac{kT}{a} \ln \left( \frac{n_{\mathrm{2}}}{n_{\mathrm{1}}} \right) \end{split}$$

# Band bending as a function of carrier concentration



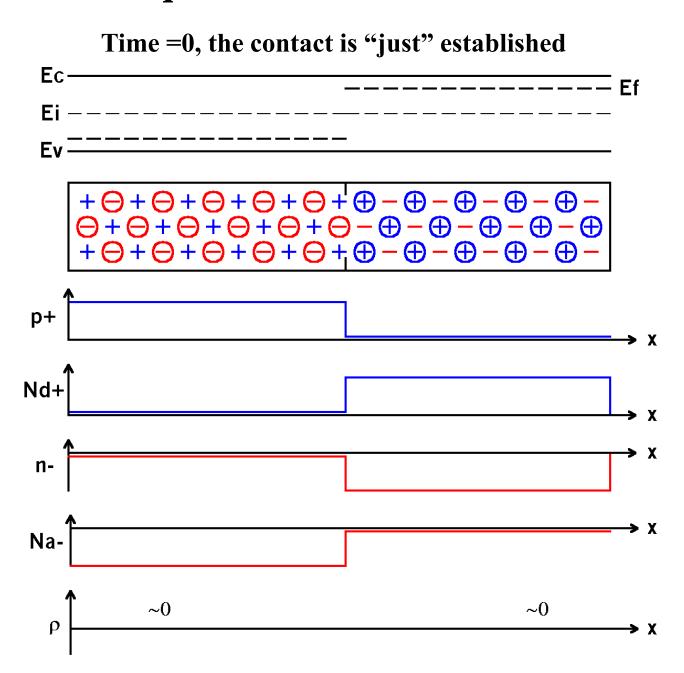
# **Lecture: P-N junction**

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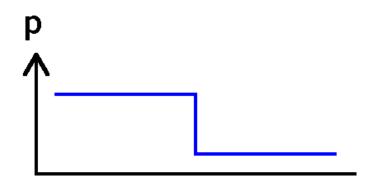
What happens when these bandstructures come into contact?

- Fermi energy must be constant at equilibrium, so bands must bend near the interface
- Far from the interface, bandstructures are conserved

P-type piece N-type piece Time < 0, i.e. before the contact is established p+ Nd+ Nd+ Na-



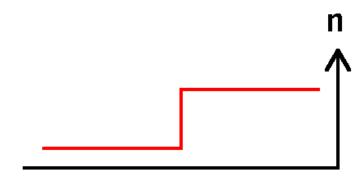
Hole gradient



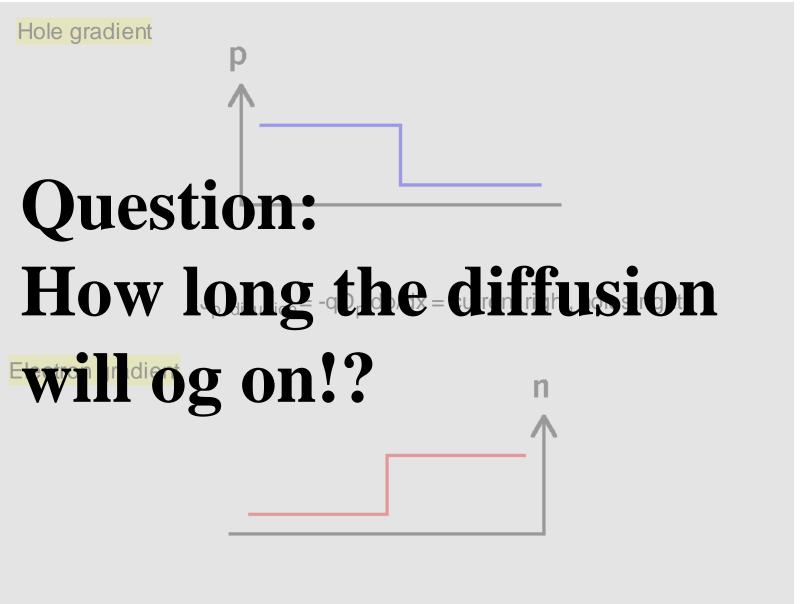
Question: How

 $J_{p, diffusion} = -qD_p dp/dx = current right, holes right$ 

Electron gradient

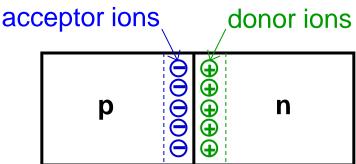


 $J_{n,diffusion} = qD_n dn/dx = current right, electrons left$ 



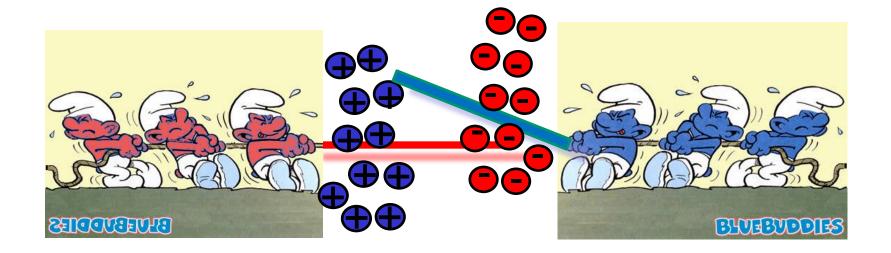
 $J_{n,diffusion} = qD_n dn/dx = current right, electrons left$ 

- When the junction is first formed, mobile carriers diffuse across the junction (due to the concentration gradients)
  - Holes diffuse from the p side to the n side, leaving behind negatively charged immobile acceptor ions
  - Electrons diffuse from the n side to the p side, leaving behind positively charged immobile donor ions

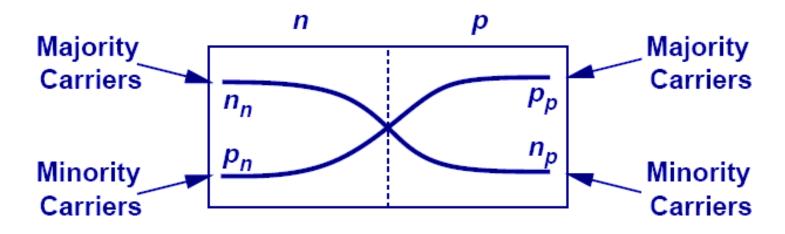


#### → A region depleted of mobile carriers is formed at the junction.

 The space charge due to immobile ions in the depletion region establishes an electric field that opposes carrier diffusion.





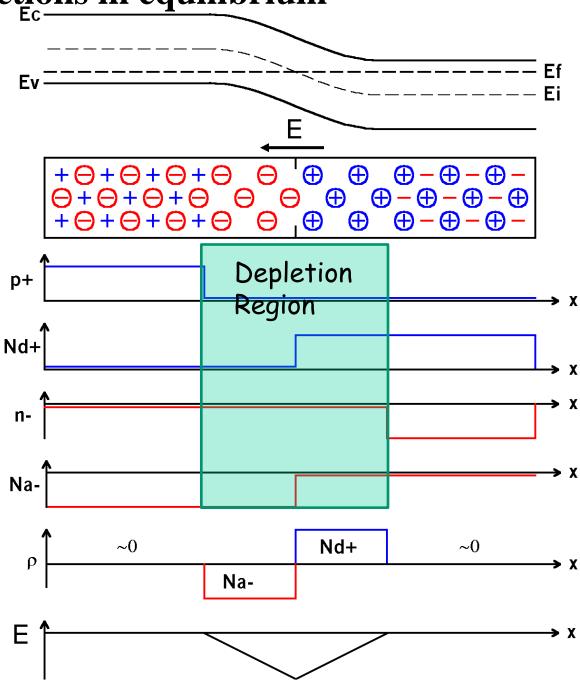


n<sub>n</sub>: Concentration of electrons on n side

P<sub>n</sub>: Concentration of holes on n side

p<sub>p</sub>: Concentration of holes on p side

n<sub>p</sub> : Concentration of electrons on p side



How big is the built-in voltage?

$$qV_{bi} = (E_i - E_F)_{Left} + (E_F - E_i)_{Right}$$

$$P \text{ side}$$

$$Ec \xrightarrow{\qquad \qquad \qquad } Ec \xrightarrow{\qquad \qquad } Ef$$

$$Ev \xrightarrow{\qquad } Ef$$

$$Ev \xrightarrow{\qquad$$

How big is the built-in voltage?

$$V_{bi} = \frac{kT}{q} \ln \left( \frac{N_a}{n_i} \right) + \frac{kT}{q} \ln \left( \frac{N_d}{n_i} \right)$$

$$\Rightarrow V_{bi} = \frac{kT}{q} \ln \left( \frac{N_a N_d}{n_i^2} \right)$$

N<sub>a</sub> acceptor level on the p side

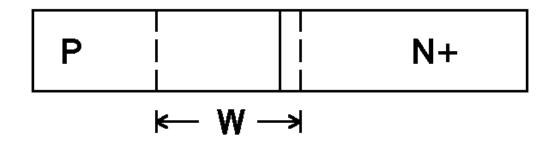
N<sub>d</sub> donor level on the n side

- One side of the junction is heavily doped, so that the Fermi level is close to the band edge.
- e.g. p<sup>+</sup>-n junction (heavy B implant into lightly doped Si substrate)

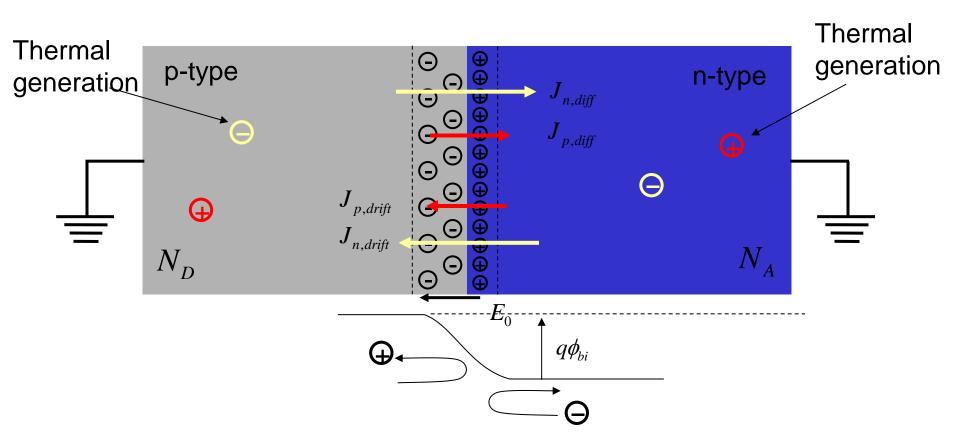
$$(E_i - E_F)_{Left} \approx E_i - E_V = E_G/2$$
  
 $(E_F - E_i)_{Right} = kT \ln \left(\frac{N_D}{n_i}\right)$ 

$$\Rightarrow V_{bi} = \frac{E_G}{2q} + \frac{kT}{q} \ln \left( \frac{N_d}{n_i} \right)$$

"P-N+" 
$$\Rightarrow$$
 N  $a \ll N_d$ 



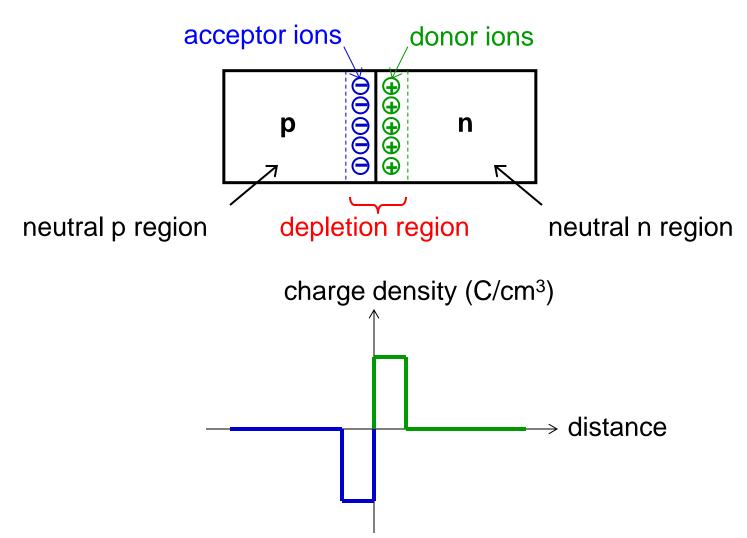
 $\leftarrow W \rightarrow$ 



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#### Charge is stored in the depletion region.



Gauss's law describes the relationship between the charge density and the electric field.

$$\iint_{S} \vec{E} \cdot d\vec{A} = \frac{1}{\varepsilon} \iint_{V} \rho \cdot dV = \frac{Q_{encl}}{\varepsilon}$$

$$\frac{dE}{dx} = \frac{\rho}{\varepsilon}$$

$$\frac{dE}{dx} = \frac{\rho}{\varepsilon} \left| E(x) - E(x_0) = \frac{1}{\varepsilon} \int_{x_0}^{x} \rho(x) dx \right|$$

Poisson's equation describes the relationship between the electric field distribution and the electric potential

$$\phi(x) - \phi(x_0) = \int_{x_0}^{x} -E(x)dx$$

Gauss and Poisson equations in one dimension

$$\frac{d^2\phi(x)}{dx^2} = -\frac{dE(x)}{dx} = -\frac{\rho(x)}{\varepsilon}$$

$$\rho_{0}(x) \approx \begin{cases} -qN_{a} & \left(-x_{p0} \le x \le 0\right) \\ qN_{d} & \left(0 \le x \le x_{n0}\right) \end{cases} \text{ and } \rho_{0}(x) = 0 \quad \left(x < -x_{p0}, \ x > x_{n0}\right) \end{cases}$$

$$E_{0}(x) = \frac{-qN_{a}}{\varepsilon_{s}}(x + x_{p0}) \quad \left(-x_{p0} < x < 0\right)$$

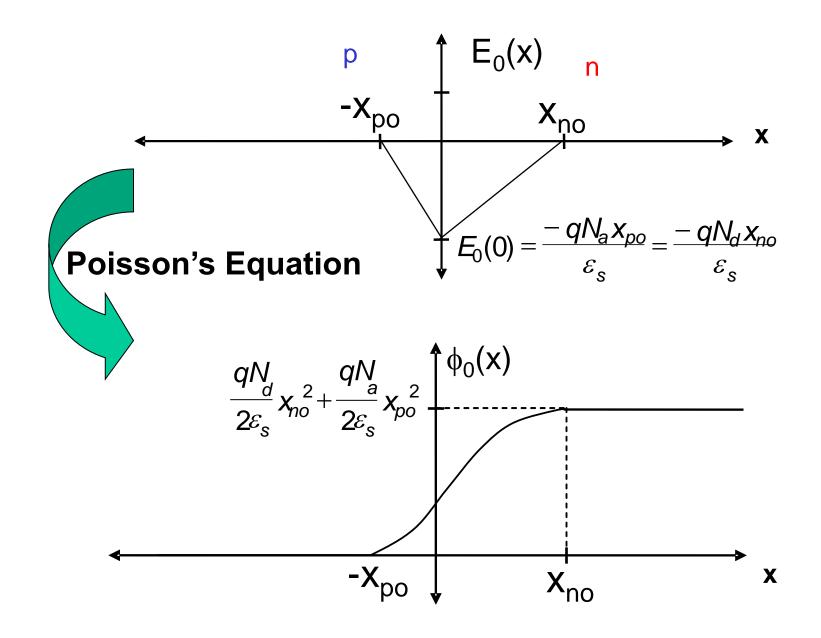
$$E_{0}(x) = \int_{x}^{x_{n0}} \frac{\rho_{0}(x)}{\varepsilon_{s}} dx - E_{0}(x_{n0}) = \frac{-qN_{d}}{\varepsilon_{s}}(x_{n0} - x) - 0 \end{cases}$$

$$E_{0}(x) = \frac{qN_{d}}{\varepsilon_{s}}(x - x_{n0})$$

$$(0 < x < x_{n0})$$

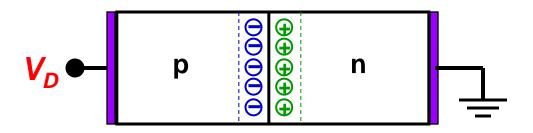
$$\rho_{0}(x) = 0 \quad \left(x < -x_{p0}, \ x > x_{n0}\right)$$

$$-x_{p0} \quad -x_{p0} \quad -$$

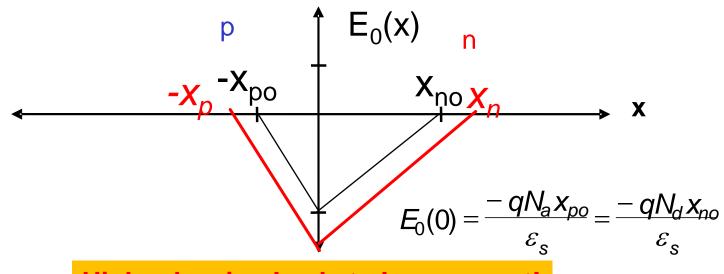


# **Lecture: P-N junction**

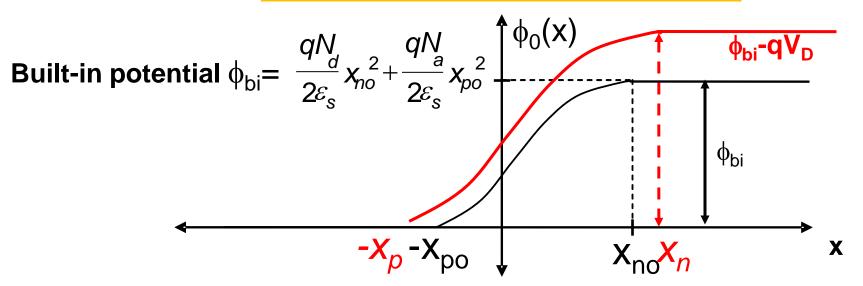
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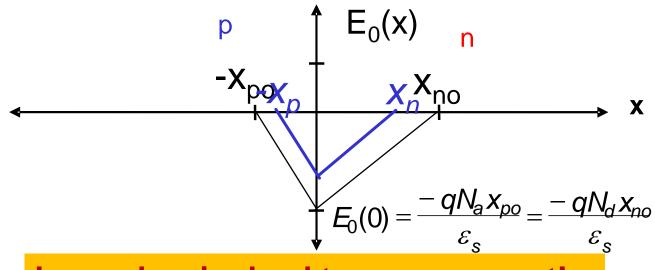


- The quasi-neutral p and n regions have low resistivity, whereas the depletion region has high resistivity. Thus, when an external voltage  $V_D$  is applied across the diode, almost all of this voltage is dropped across the depletion region.
- If  $V_D > 0$  (forward bias), the potential barrier to carrier diffusion is reduced by the applied voltage.
- If  $V_D < 0$  (*reverse bias*), the potential barrier to carrier diffusion is increased by the applied voltage.

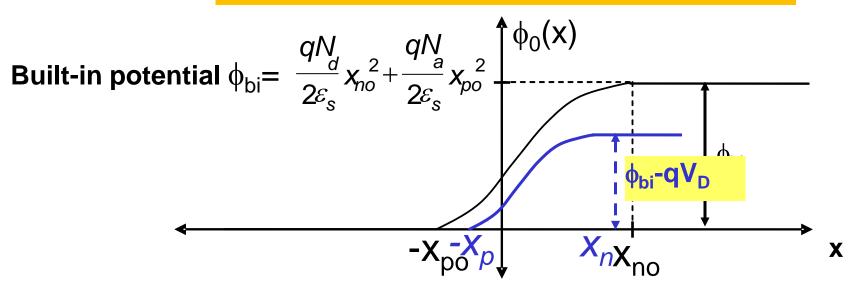


**Higher barrier leads to less current!** 

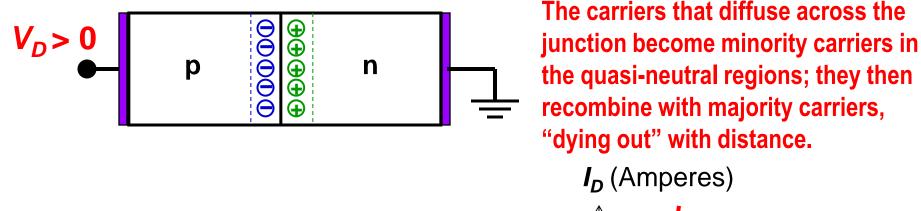


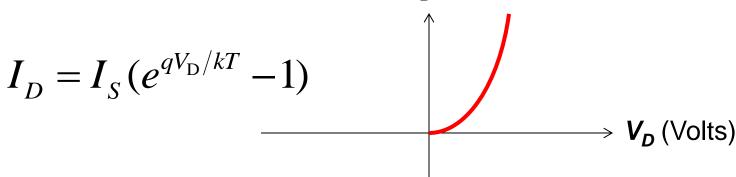


#### Lower barrier lead to more current!



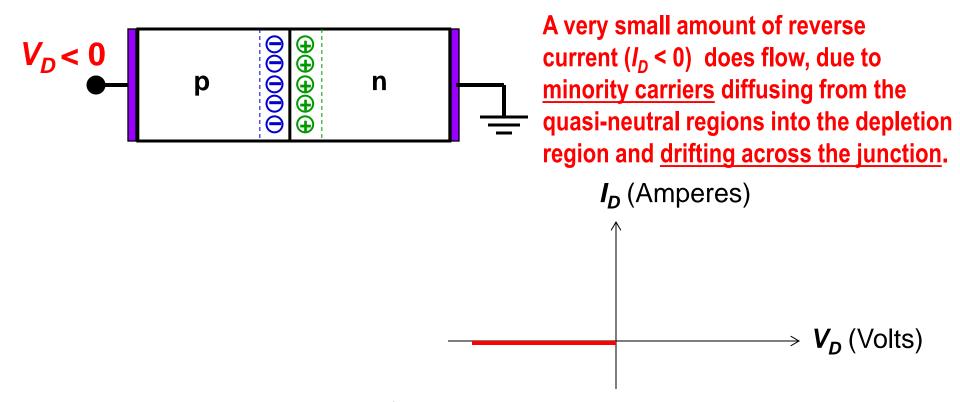
 As V<sub>D</sub> increases, the potential barrier to carrier diffusion across the junction decreases\*, and current increases exponentially.



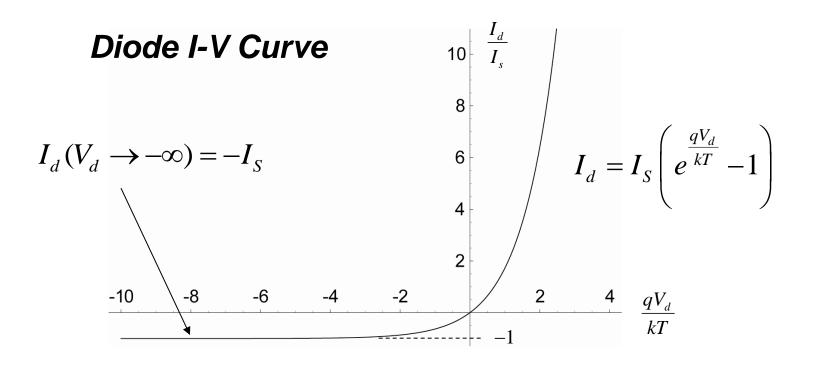


\* Hence, the width of the depletion region decreases.

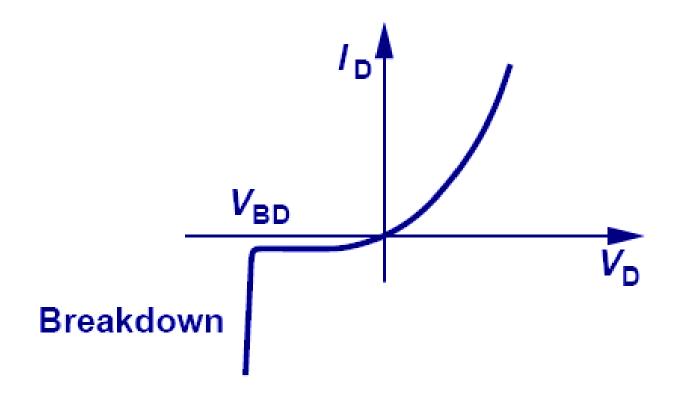
• As  $|V_D|$  increases, the potential barrier to carrier diffusion across the junction increases\*; thus, no carriers diffuse across the junction.



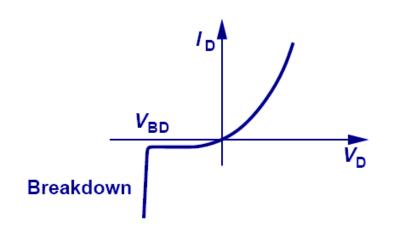
<sup>\*</sup> Hence, the width of the depletion region increases.



- Diode IV relation is an exponential function
- This exponential is due to the Boltzmann distribution of carriers versus energy
- For reverse bias the current saturations to the drift current due to minority carriers



When a large reverse bias voltage is applied, breakdown occurs and current flows through the diode increases dramatically.



When a large reverse bias voltage is applied, breakdown occurs and current flows through the diode increases dramatically.

- Zener breakdown or tunneling mechanism, occurs in a highly doped p-n junction, while the conduction and valance bands on opposite sides of the junction become so close during the reverse-bias that the electrons on the p-side can tunnel from directly VB into the CB on the n-side.
- Avalanche breakdown mechanism occurs when electrons and holes moving through the depletion region and acquire sufficient energy from the electric field to break a bond i.e. create electron-hole pairs by colliding with atomic electrons within the depletion region. These newly created electrons and holes move in opposite directions due to the electric field and thereby add to the existing reverse bias current.